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THE UNITED STATES PATENT AND TRADEMARK OFFICE  
Applicant: Choi et al. PATENT APPLICATION  
Serial No.: 09/698,317 Group Art Unit: 2859  
Filing Date: October 27, 2000 Examiner: Unassigned  
For: HIGH-PRECISION ORIENTATION ALIGNMENT AND GAP CONTROL STAGES  
FOR IMPRINT LITHOGRAPHY PROCESSES

INFORMATION DISCLOSURE STATEMENT

Commissioner  
for Patents  
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Sir:

The following information is submitted in compliance with Applicants' duty of disclosure under 37 C.F.R. § 1.56. Form PTO-1449 and a copy of each reference recited below accompanies this document. It is respectfully requested that the cited information be expressly considered during the prosecution of this application, and the references be made of record therein and appear among the "references cited" on any patent to issue therefrom.

ISSUED PATENTS

<u>Patent Number</u>	<u>Inventor</u>	<u>Grant Date</u>
4,440,804	Milgram	Apr. 3, 1984
4,544,572	Sandvig et al.	Oct. 1, 1985
5,723,176	Keyworth et al.	Mar. 3, 1998
5,747,102	Smith et al.	May 5, 1998
6,125,183	Jiawook et al.	Sep. 26, 2000

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FOREIGN PATENT DOCUMENTS

<u>Document Number</u>	<u>Inventor</u>	<u>Pub. Date</u>
WO 92/17883	Olsson	Oct. 15, 1992
WO 98/10121	Olsson et al.	Mar. 12, 1998
WO 99/45753	Wikström	Sep. 10, 1999
WO 99/63535	Olsson	Dec. 9, 1999

NON-PATENT DOCUMENTS

Lin, "Multi-Layer Resist Systems", Introduction of Microlithography", American Chemical Society, 1983, pp. 287-350, IBM T.J. Watson Research Center, Yorktown Heights, NY 10598.

Cowie, "Polymers: Chemistry and Physics of Modern Materials", 1991, pp. 408-409, 2<sup>nd</sup> Ed, Chapman and Hall, a division of Routledge, Chapman and Hall, Inc., 29 West 35<sup>th</sup> Street, NY, NY 10001-2291.

Chou et al., "Imprint of Sub-25nm Vias and Trenches in Polymers", Applied Physics Letters, Nov. 20, 1995, pp. 3114-3116, vol. 67(21).

Chou et al., "Imprint Lithography with 25-Nanometer Resolution", Science, Apr. 5, 1996, pp. 85-87, vol. 272.

Chou et al., "Imprint Lithography with Sub-10nm Feature Size and High Throughput", Microelectronic Engineering, 1997, pp. 237-240, vol. 35.

Xia et al., "Soft Lithography", Agnew. Chem. Int. Ed., 1998, pp.  
550-575, vol. 37.

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*02.20.03*

Respectfully Submitted,

*Kenneth C. Brooks*

Kenneth C. Brooks

Reg. No. 38,393

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<b>Application Number</b>	09/698,317
<b>Filing Date</b>	October 27, 2000
<b>First Named Inventor</b>	Choi et al.
<b>Group Art Unit</b>	2859
<b>Examiner Name</b>	Unassigned
<b>Attorney Docket Number</b>	PA09-06V02

(use as many sheets as necessary)

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of

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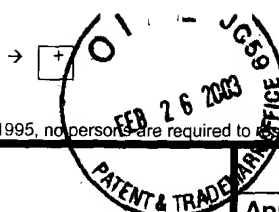
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			Filing Date	October 27, 2000
			First Named Inventor	Choi et al.
			Group Art Unit	2859
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			Attorney Docket Number	PA09-06V02
Sheet	2	of	2	

OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS			
Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T <sup>2</sup>
	B10	LIN, "Multi-Layer Resist Systems", Introduction of Microlithography", American Chemical Society, 1983, pp. 287-350, IBM T.J. Watson Research Center, Yorktown Heights, New York 10598.	
	B11	COWIE, "Polymers: Chemistry and Physics of Modern Materials", 1991, pp. 408-409, 2 <sup>nd</sup> Ed, Chapman and Hall, a division of Routledge, Chapman and Hall, Inc., 29 West 35 <sup>th</sup> Street, NY, NY 10001-2291.	
	B12	CHOU et al., "Imprint of Sub-25 nm Vias and Trenches in Polymers", Applied Physics Letters, November 20, 1995, pp. 3114-3116, vol. 67(21).	
	B13	CHOU et al., "Imprint Lithography with 25-Nanometer Resolution", Science, Apr. 5, 1996, pp. 85-87, vol. 272.	
	B14	CHOU et al., "Imprint Lithography with Sub-10nm Feature Size and High Throughput", Microelectronic Engineering, 1997, pp. 237-240, vol. 35.	
	B15	XIA et al., "Soft Lithography", Agnew. Chem. Int. Ed., 1998, pp. 550-575, vol. 37.	

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